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(54) **EMBEDDED NONVOLATILE MEMORY**

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H01L 29/423 (2006.01)
H01L 21/28 (2006.01)
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H01L 21/3205 (2006.01)
H01L 21/3213 (2006.01)
H01L 21/311 (2006.01)
H01L 21/02 (2006.01)

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CPC **H01L 29/7883** (2013.01); **H01L 21/0217**

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H01L 29/66825 (2013.01)

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CPC H01L 2924/0002; H01L 2924/00;
H01L 27/0207; H01L 27/11807; H01L
27/1104
USPC 257/211, 314, 324, 326, 321
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* cited by examiner

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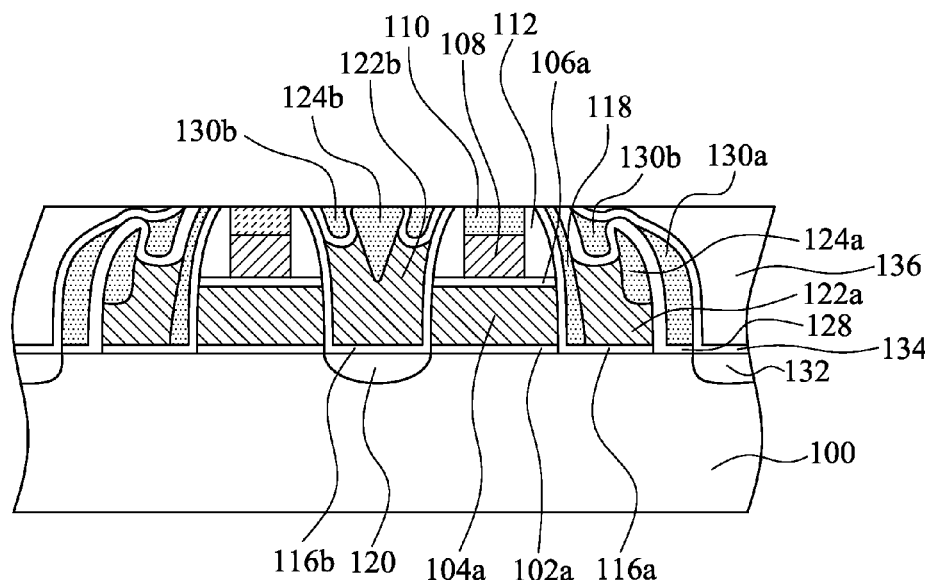
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(57) **ABSTRACT**

A nonvolatile memory embedded in an advanced logic circuit and a method forming the same are provided. In the nonvolatile memory, the word lines and erase gates have top surfaces lower than the top surfaces of the control gate. In addition, the word lines and the erase gates are surrounded by dielectric material before a self-aligned silicidation process is performed. Therefore, no metal silicide can be formed on the word lines and the erase gate to produce problems of short circuit and current leakage in a later chemical mechanical polishing process.

20 Claims, 8 Drawing Sheets



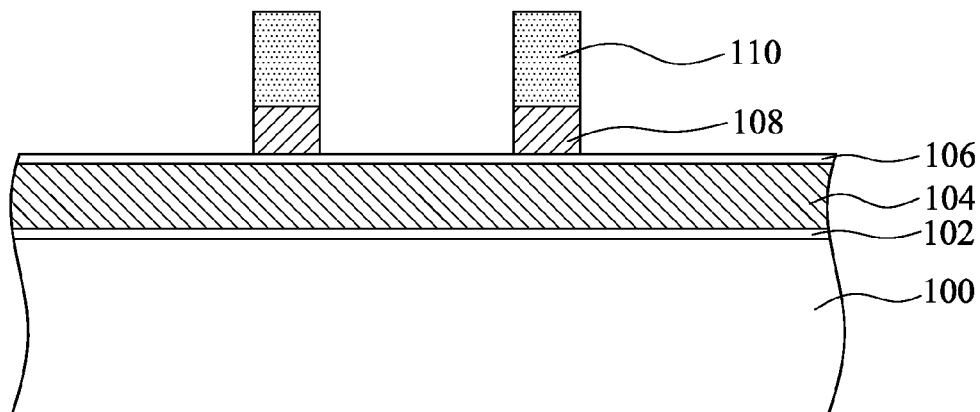


Fig. 1A

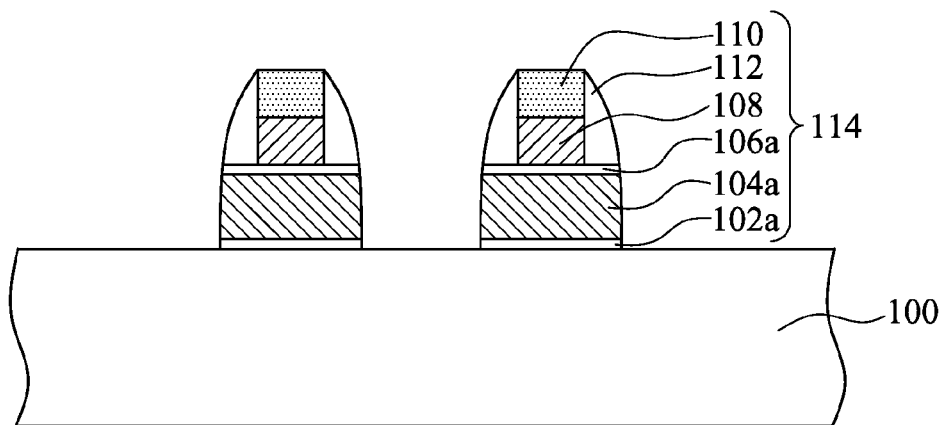


Fig. 1B

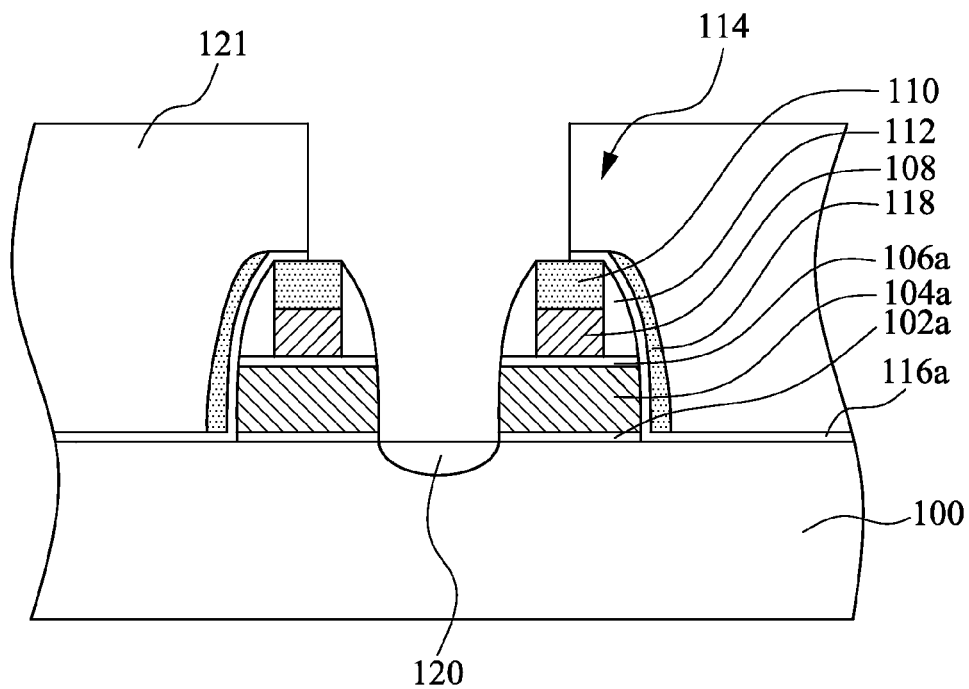


Fig. 1C

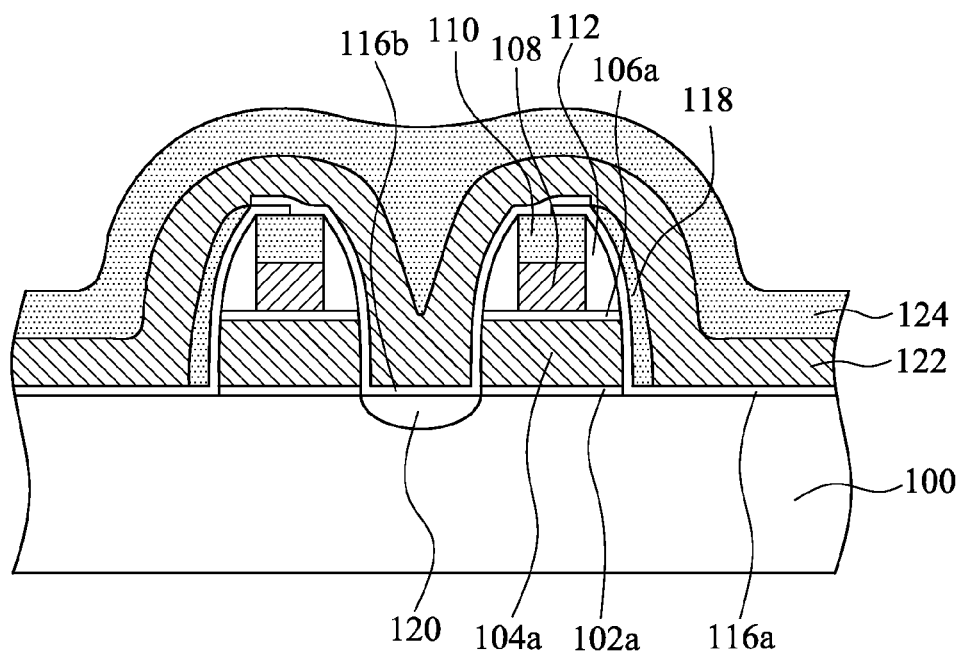


Fig. 1D

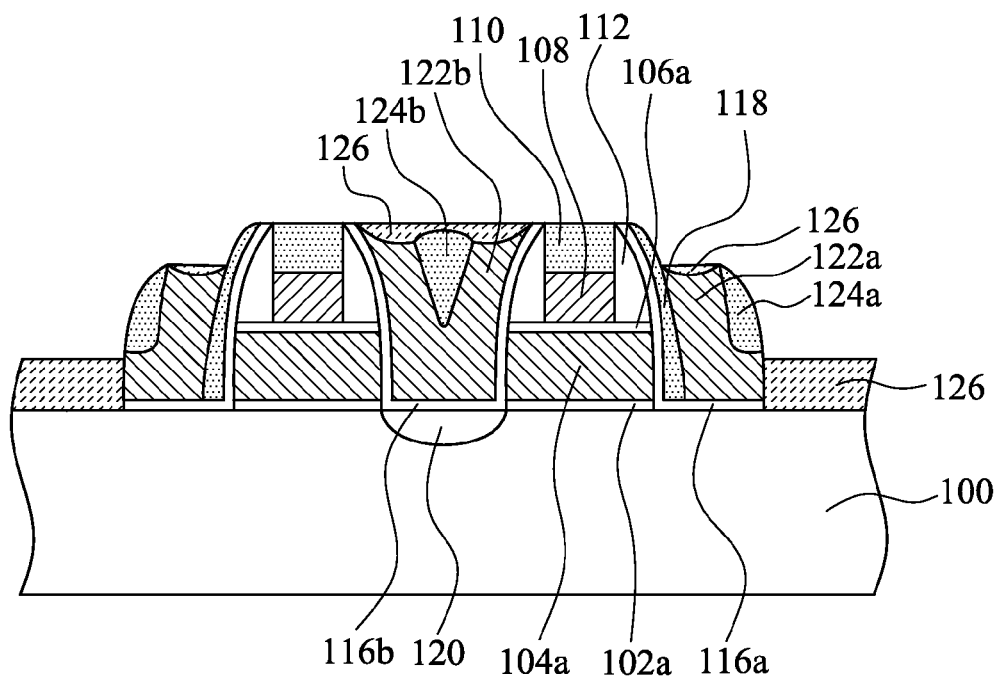


Fig. 1E

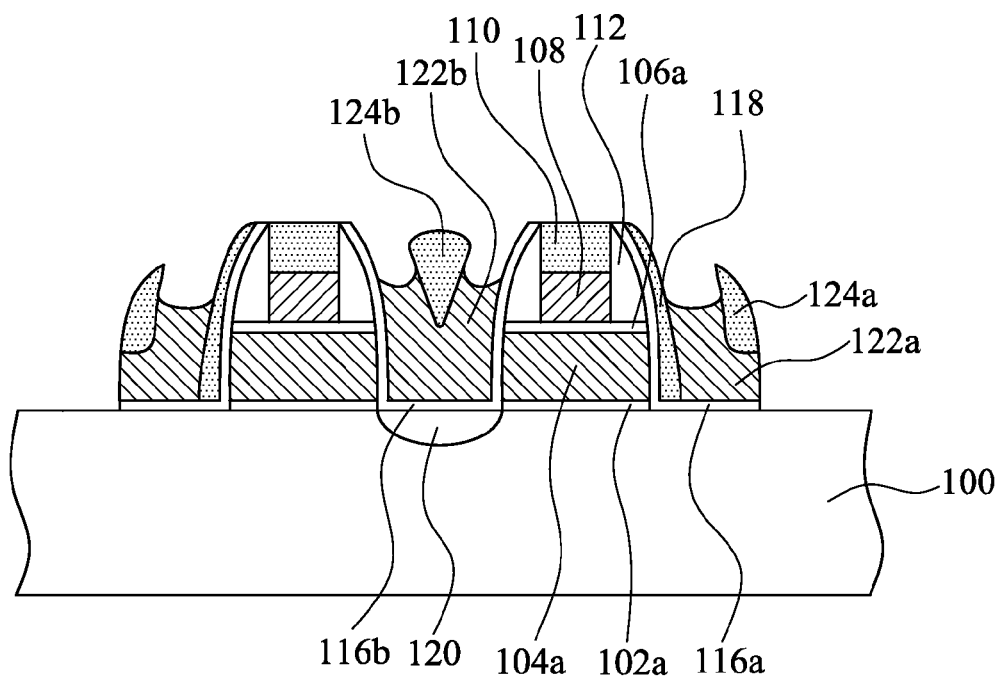


Fig. 1F

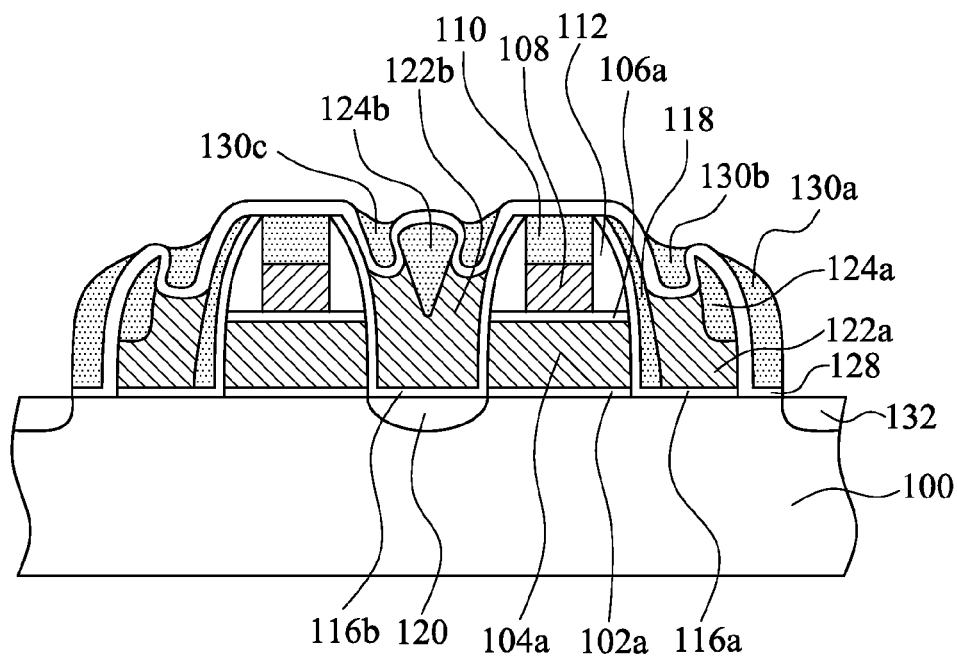


Fig. 1G

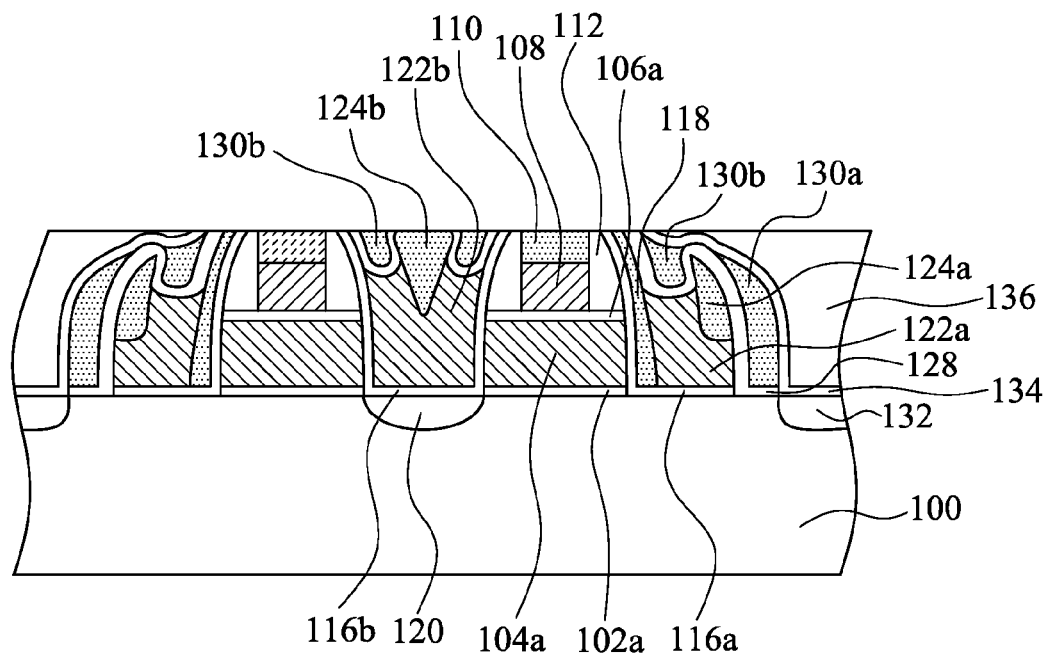


Fig. 1H

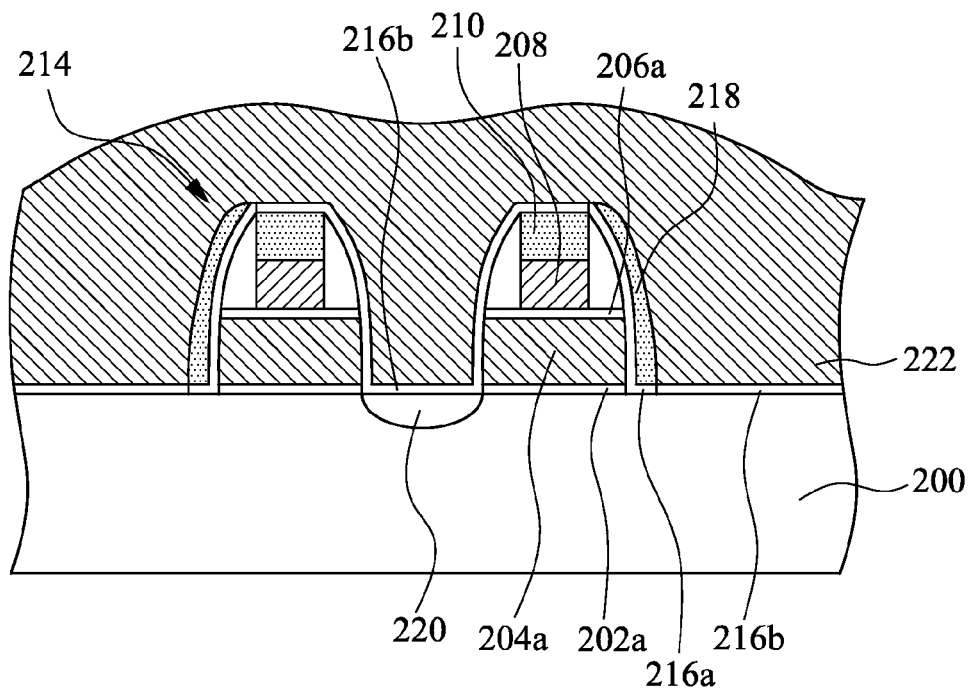


Fig. 2A

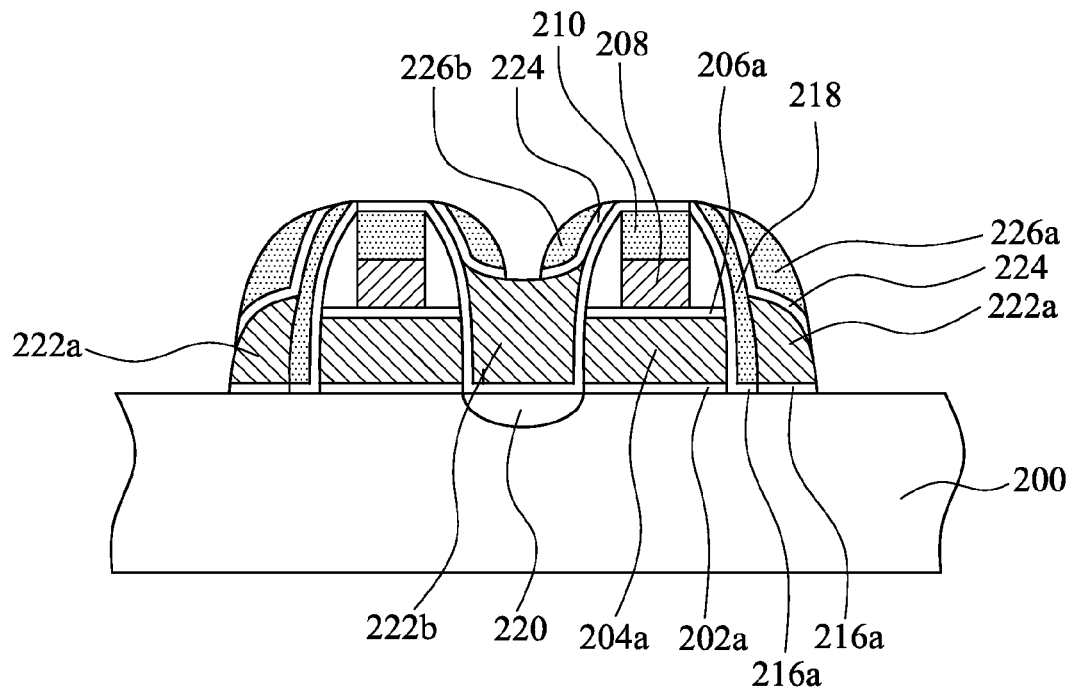


Fig. 2B

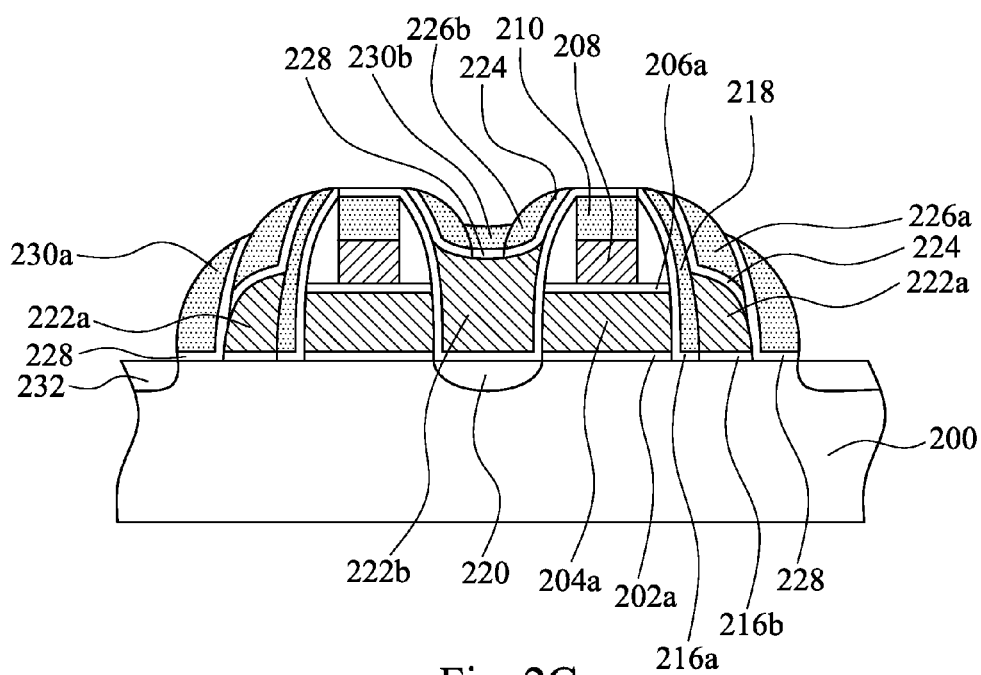


Fig. 2C

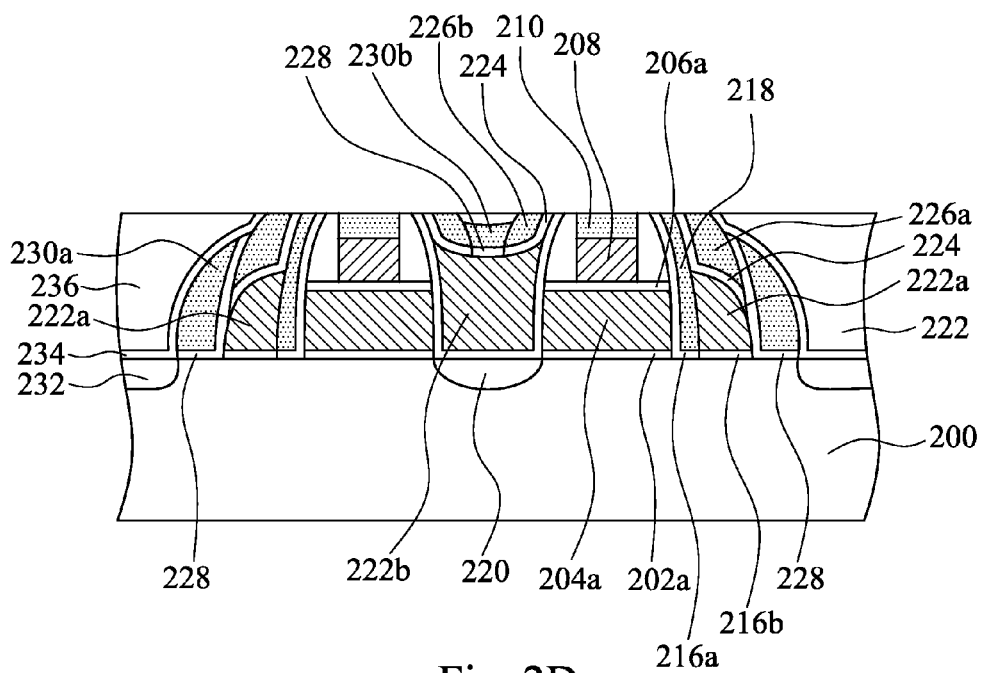


Fig. 2D

Fig. 3B

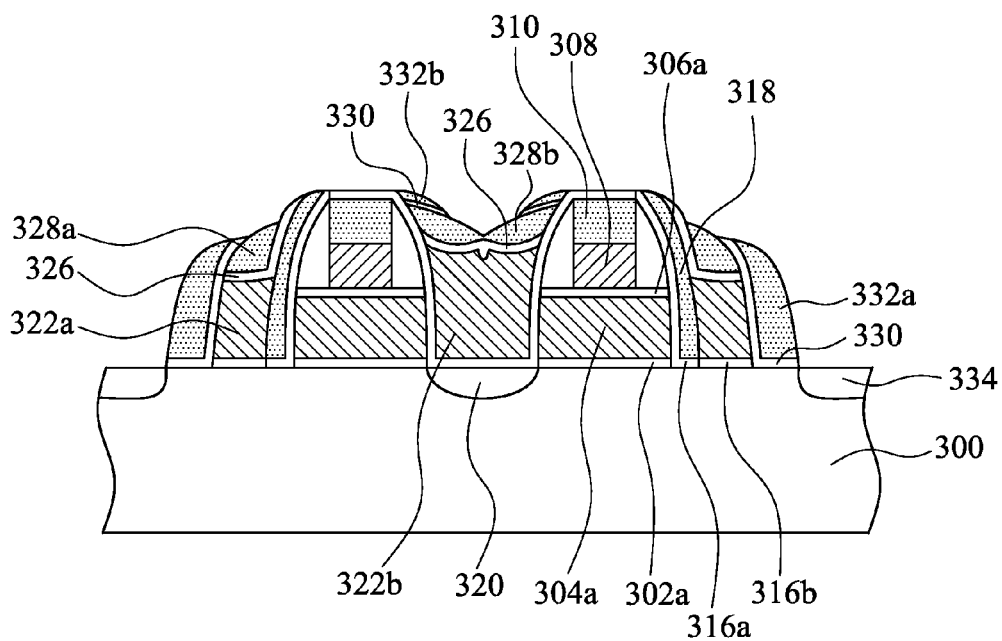


Fig. 3C

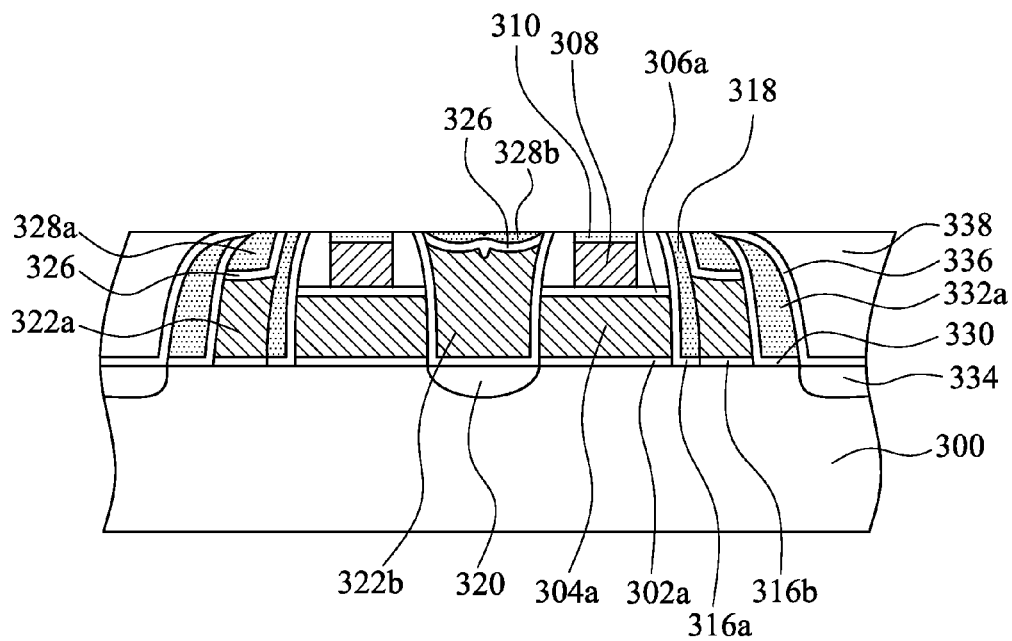


Fig. 3D

EMBEDDED NONVOLATILE MEMORY

BACKGROUND

The functionality and performance of an advanced logic circuit for mobile applications can be further enhanced by embedding nonvolatile memory with the advanced logic circuit. However, some problems still need to be solved to integrate a process of a nonvolatile memory with an advanced logic circuit.

BRIEF DESCRIPTION OF THE DRAWINGS

Aspects of the present disclosure are best understood from the following detailed description when read with the accompanying figures. It is noted that, in accordance with the standard practice in the industry, various features are not drawn to scale. In fact, the dimensions of the various features may be arbitrarily increased or reduced for clarity of discussion.

FIGS. 1A-1H are cross-sectional diagrams showing a process of embedded nonvolatile memory according to some embodiments of this disclosure.

FIGS. 2A-2D are cross-sectional diagrams showing a process of embedded nonvolatile memory according to some other embodiments of this disclosure.

FIGS. 3A-3D are cross-sectional diagrams showing a process of embedded nonvolatile memory according to some other embodiments of this disclosure.

The drawings, schematics and diagrams are illustrative and not intended to be limiting, but are examples of embodiments of the disclosure, are simplified for explanatory purposes, and are not drawn to scale.

DETAILED DESCRIPTION

The following disclosure provides many different embodiments, or examples, for implementing different features of the provided subject matter. Specific examples of components and arrangements are described below to simplify the present disclosure. These are, of course, merely examples and are not intended to be limiting. For example, the formation of a first feature over or on a second feature in the description that follows may include embodiments in which the first and second features are formed in direct contact, and may also include embodiments in which additional features may be formed between the first and second features, such that the first and second features may not be in direct contact. In addition, the present disclosure may repeat reference numerals and/or letters in the various examples. This repetition is for the purpose of simplicity and clarity and does not in itself dictate a relationship between the various embodiments and/or configurations discussed.

Further, spatially relative terms, such as “beneath,” “below,” “lower,” “above,” “upper” and the like, may be used herein for ease of description to describe one element or feature’s relationship to another element(s) or feature(s) as illustrated in the figures. The spatially relative terms are intended to encompass different orientations of the device in use or operation in addition to the orientation depicted in the figures. The apparatus may be otherwise oriented (rotated 90 degrees or at other orientations) and the spatially relative descriptors used herein may likewise be interpreted accordingly.

One problem of integrating nonvolatile memory process with an advanced logic process for mobile applications is caused by forming metal silicide on the top of the word lines and erase gates in the nonvolatile memory area when metal

silicide is formed on the source/drain regions of the logic area. After chemical mechanical polishing process, the metal silicide on the top of the word lines will be spread over the entire wafer and problems of short circuit and current leakage are thus produced. Therefore, this disclosure provides a novel process of manufacturing nonvolatile memory that can be integrated with an advanced logic process for mobile applications to solve the problem above. According various embodiments of this disclosure, the nonvolatile memory may be a stacked gate memory.

FIGS. 1A-1H are cross-sectional diagrams showing a process of embedded nonvolatile memory according to some embodiments of this disclosure. In FIGS. 1A-1H, the word lines **122a** and the erase gates **122b** of the nonvolatile memory formed in FIG. 1E will be etched back in FIG. 1F. Thus, the top surfaces of the word lines **122a** and the erase gates **122b** is not higher than the top surfaces of the control gates **108** to avoid forming metal silicide on the top surfaces of the word lines **122a** and the erase gates **122b**.

In FIG. 1A, a tunneling oxide layer **102** and a first polysilicon layer are sequentially formed on a substrate **100**, which has isolation structures (not shown in FIG. 1A) formed therein. The first polysilicon layer is then patterned to form plural polysilicon stripes **104** paralleling to the surface of the paper. The isolation structures above may be shallow trench isolations (STIs), for example. The tunneling oxide layer **102** may be formed by a thermal oxidation process. The first polysilicon layer may be formed by chemical vapor deposition and then be patterned by photolithography and followed by dry etching, for example, to form the plural polysilicon stripes **104**. The first polysilicon may have a thickness of 150-300 Å, such as 200 Å.

Next, a middle dielectric layer **106**, a second polysilicon layer, and a first dielectric layer are sequentially formed above the substrate **100** to cover the plural polysilicon stripes **104** and the tunneling oxide layer **102**. The middle dielectric layer **106** may include a bottom silicon oxide layer, a middle silicon nitride layer, and a top silicon oxide layer, for example. The bottom and top silicon oxide layers may be formed by thermal oxidation at a temperature of 800-1200° C. followed by annealing at 1000° C., and may have a thickness of 40 Å, for example. The middle silicon nitride layer may be formed by low pressure chemical vapor deposition (LPCVD), and may have a thickness of 80 Å, for example. The second polysilicon layer may be formed by chemical vapor deposition and have a thickness of 300-600 Å, such as 250 Å. The first dielectric layer may be made of silicon nitride deposited by LPCVD and have a thickness of 1000-1500 Å, such as 1300 Å.

Then, the first dielectric layer and the second polysilicon layer are patterned to form mask layers **110** and control gates **108**, respectively. The patterning method may be performed by photolithography and followed by dry etching. During the etching of the second polysilicon layer, the mask layers **110** are used as an etching mask.

In FIG. 1B, a second dielectric layer is formed above the substrate **100** to conformally cover the mask layers **110**, the control gates **108** and the middle dielectric layer **106**. Next, the second dielectric layer is anisotropically etched to form first spacers **112** on the sidewalls of the mask layers **110** and the control gates **108**. Subsequently, the exposed middle dielectric layer **106**, the plural polysilicon stripes **104** and the tunneling oxide layer **102** thereunder are etched to form the middle dielectric layer **106a**, the floating gate **104a**, and the tunneling oxide layer **102a** to form gate stacks **114** on the

substrate **100**. The second dielectric layer may include a bottom silicon oxide layer, a middle silicon nitride layer, and a top silicon oxide layer.

In FIG. 1C, a first buffer layer **116a** and a third dielectric layer are sequentially formed above the substrate **100** to conformally cover the exposed surfaces of the gate stacks **114** and the exposed substrate **100**. The first buffer layer **116a** may be a silicon oxide layer formed by chemical vapor deposition, for example. The third dielectric layer may be a silicon nitride layer formed by LPCVD, for example. The third dielectric layer is then anisotropically etched to form second spacers **118** on sidewalls of the gate stacks **114**. The anisotropic etch may be performed by dry etching.

The first buffer layer **116a** above is usually used to release the strains caused by lattice mismatch between the third dielectric layer and the exposed silicon layers when the lattice mismatch above is obvious. For example, the exposed silicon layers include the floating gates **104a** and the substrate **100** in FIG. 1C. However, if the lattice mismatch between the third dielectric layer and the exposed silicon layers is not so obvious to generate obvious strains, the first buffer layer **116a** may be omitted.

Next, a patterned photoresist layer **121** is formed by a combination of spin coating, exposing and developing processes to expose the common source area of the substrate **100**. Ions are then implanted into the exposed substrate **100** to form the common source **120**. Subsequently, the second spacers **118** exposed by the patterned photoresist layer **121** is removed, and the removal method may be performed by dry etching or wet etching, for example. During the removal of the exposed second spacers **118**, the first buffer layer **116a** may be consumed finally to expose the common source **120**.

In FIG. 1D, the patterned photoresist layer **121** is removed, and the removal method may be performed by solvent stripping or plasma ashing, for example. Then, a gate oxide layer **116b** is formed to cover the exposed substrate **100**, i.e. the common source **120**. The gate oxide layer **116b** may be formed by thermal oxidation.

Next, a third polysilicon layer **122** and a fourth dielectric layer **124** are sequentially formed above the substrate **100**. The thickness of the third polysilicon layer **122** is smaller than a total thickness of the tunneling oxide layer **102a**, the floating gate **104a**, the middle dielectric layer **106a**, and the control gates **108**, such as in a range from about 400 Å to about 600 Å. The thickness of the fourth dielectric layer **124** is in a range from about 200 Å to about 400 Å. The fourth dielectric layer **124** may be made of silicon oxide formed by LPCVD, for example.

In FIG. 1E, the fourth dielectric layer **124** is anisotropically etched to form first side cap layers **124a** on the word lines **122a** and first middle cap layers **124b** on the erase gates **122b**, and the etching is stopped on the third polysilicon layer **122**. Subsequently, the exposed third polysilicon layer **122** is anisotropically etched to form word lines **122a** next to the second spacers **118** and erase gate **122b** above the common source **120**, and the etching is stopped on the first buffer layer **116a**. The anisotropic etching above may be performed by dry etching.

Please noted that since the first buffer layer **116a** is quite thin, and thus the exposed portions of the first buffer layer **116a** may be easily etched away to expose the substrate **100** thereunder during the etching of the third polysilicon layer **122**. Therefore, an organic material is spin coated above the substrate **100** to form an organic layer **126** covering the exposed top surface of the substrate **100** to protect the exposed substrate **100**. Simultaneously, since the exposed top surfaces of the word lines **122a** and the erase gate **122b** are

etched to have a concave top surface, the organic material also can be spin coated on the top surfaces of the word lines **122a** and the erase gate **122b**. In addition, the thickness of the organic layer **126** covering the substrate **100** is more than the thickness of the organic layer **126** covering the word lines **122a** and the erase gate **122b** to provide a better protection to the substrate **100**. The organic material above may be photoresist or other organic polymers that can be spin-coated to protect the exposed substrate **100** during the subsequent etching of the word lines **122a** and the erase gate **122b**.

In FIG. 1F, the organic layer **126** is etched to expose the top surfaces of the word lines **122a** and the erase gate **122b**, but the top surface of the substrate **100** is still covered by the organic layer **126**. Next, the exposed word lines **122a** and the exposed erase gate **122b** are selectively etched back by isotropic dry etching to avoid damaging the second spacers **118**, the first side cap layers **124a** and the first middle cap layers **124b** made of silicon nitride. Therefore, the level of the top surfaces of the word lines **122a** and the erase gate **122b** are lowered. Then, the remained organic layer **126** on the substrate **100** is removed by solvent stripping, for example.

According to some embodiments, the isotropic dry etching above may be performed by an inductively-coupled plasma (ICP) poly etcher. The source of the etching plasma may include a mixture of 5-50 sccm of SF₆ and 100-600 sccm of a carrier gas, and the carrier gas may be Ar or He. The pressure in the reactive chamber may be increased to 3-50 mTorr, and the ICP power may be increased to 200-600 W. In addition, the bias voltage may be decreased to 0-100 V. Since SF₆ is used as the source of the etching plasma, the dry etching can be isotropic.

According to some other embodiments, the dry etching above may be performed by a chemical dry etcher. The chemical dry etcher equipped with a remote plasma source to decrease the kinetic energy of the generated plasma to almost zero. Therefore, an isotropic etching can be performed to decrease the damage caused by high kinetic energy plasma. In the chemical dry etching (CDE) process, the source of the plasma may include a mixture of C_xH_yF_z and oxygen. The total flow rate of the mixture gas may be 300-800 sccm, and the flow rate ratio of the C_xH_yF_z to oxygen may be 0.5-1.5. The C_xH_yF_z may be CH₂F₂, CHF₃, CF₄, C₂F₆, C₃F₈, C₄F₆, or C₅F₈. The pressure of the reactive chamber may be 200-500 mTorr. The etching selectivity of silicon over silicon nitride is about 3-10, and thus the damage of the second spacers **118**, the first side cap layers **124a** and the first middle cap layers **124b** may be effectively decreased.

In FIG. 1G, a second buffer layer **128** and a fifth dielectric layer are sequentially formed above the substrate **100** to cover the structures on the substrate **100**. The fifth dielectric layer is then anisotropically etched to form third spacers **130a** on sidewalls of the word lines **122a**, second side cap layers **130b** on the top surface of the word lines **122a** and second middle cap layers **130c** on the erase gate **122b**. At the same time, the exposed second buffer layer **128** is also etched away during the etching of the fifth dielectric layer, since the second buffer layer **128** is kind of thin. The second buffer layer **128** may be a silicon oxide layer formed by CVD. The fifth dielectric layer may be a silicon nitride layer formed by LPCVD. The anisotropic etching may be performed by dry etching, for example. Similarly, the second buffer layer **128** may be omitted when the lattice mismatch between the fifth dielectric layer and the exposed silicon layers is not obvious to create obvious strain.

Subsequently, a self-aligned silicidation (salicide) process is performed to form metal silicide on exposed surfaces of silicon material on both the nonvolatile memory area and the logic area. Therefore, metal silicide will be formed on the

exposed surfaces of the substrate **100** and other polysilicon layers. Please note that since the exposed surfaces of the word lines **122a** and the erase gate **122b** have been covered by the second buffer layer **128**, first side cap layers **124a**, first middle cap layers **124b**, third spacers **130a**, second side cap layers **130b**, and second middle cap layer **130c**, no metal silicide can be formed on the top surface of the word lines **122a** and the erase gate **122b**. In the nonvolatile memory area, metal silicide layers **132** can be formed only on the exposed surfaces of the substrate **100** to be used as drains.

In FIG. 1H, an etching stop layer **134** is formed above the substrate **100** to conformally covered the structures on the substrate **100**. The material of the etching stop layer **134** may be silicon nitride formed by LPCVD, for example. Then, a low-k dielectric layer **136** is formed above the substrate **100** to cover the structures formed on the substrate **100**. A process of chemical mechanical polishing (CMP) is subsequently performed to polish the whole wafer to remove an upper portion of the low-k dielectric layer **136**, and the CMP is stopped on the mask layer **110**. Hence, the thickness of the mask layer **110** is decreased further.

The material of the low-k dielectric layer **136** may be made from a dielectric material having a dielectric constant smaller than the dielectric constant of silicon dioxide (i.e. a low-k dielectric material). Common low-k dielectric material includes fluorine-doped silicon dioxide, carbon-doped silicon dioxide, porous silicon dioxide, porous carbon-doped silicon dioxide, a spin-on organic polymeric dielectric (such as polyimide, polynorbornenes, benzocyclobutene, or polytetrafluoroethylene), a spin-on silicone based polymeric dielectric (such as hydrogen silsesquioxane (HSQ) and methylsilsesquioxane (MSQ)).

FIGS. 2A-2D are cross-sectional diagrams showing a process of embedded nonvolatile memory according to some other embodiments of this disclosure. Since the processes before FIG. 2A are similar to FIGS. 1A-1C, the figures and the detailed descriptions are omitted here. In addition, the reference numbers in FIG. 2A representing the same or similar components are obtained by adding 100 to the reference numbers in FIG. 1C, and the meanings of the reference numbers in FIG. 2A representing the same or similar components are thus not described repeatedly. In FIGS. 2A-2D, the third polysilicon layer **122** and the fourth dielectric layer **124** in FIG. 1D is replaced by only a third polysilicon layer **222** in FIG. 2A, and the third polysilicon layer **222** is etched to form the word lines **222a** and the erase gate **222b** having top surfaces not higher than the top surfaces of the control gate **208** in FIG. 2B to avoid forming metal silicide on the top surfaces of the word lines **222a** and the erase gates **222b**. The detailed descriptions of FIGS. 2A-2D are described below.

After the removal of the photoresist layer **121** in FIG. 1C, the exposed first buffer layer **216a** is then removed in FIG. 2A. The removal method of the exposed first buffer layer **216a** may be wet etching, for example. A gate oxide layer **216b** is grown to cover the exposed surfaces of the substrate **200**, the floating gate **204a** and the common source **220**. The formation method of the gate oxide layer **216b** may be performed by thermal oxidation. Next, a third polysilicon layer **222** is formed to cover the substrate **200**, and the thickness of the third polysilicon layer **222** is greater than the total thickness of the gate stacks **214**. According to some embodiments, the thickness of the third polysilicon layer is in a range from about 1800 Å to about 2200 Å.

In FIG. 2B, the third polysilicon layer **222** is anisotropically etched until the substrate **200** is exposed to form word lines **222a** and erase gate **222b**. Then, a second buffer layer **224** and a fourth dielectric layer are sequentially formed

above the substrate **200**. The fourth dielectric layer is anisotropically etched to form side cap layers **226a** on the word lines **222a** and first middle cap layers **226b** on the erase gates **222b**, and the exposed second buffer layer **224** is consumed during the etching of the fourth dielectric layer. Next, the exposed word lines **222a** are further etched by using the side cap layer **226a** as an etching mask to modify the profile of the word lines **222a**. As for the erase gate **222b**, since the fourth dielectric layer is thicker over the erase gate **222b**, the erase gate **222b** is finally not etched during the etching back of the word lines **222a**.

In FIG. 2C, a third buffer layer **228** and a fifth dielectric layer are sequentially formed above the substrate **200**. The fifth dielectric layer is anisotropically etched to form third spacers **230a** on sidewalls of the word lines **222a** and a second middle cap layer **230b** on the erase gates **222b**. The exposed third buffer layer **228** is consumed during the etching of the fifth dielectric layer. The third buffer layer **228** may be a silicon oxide layer formed by CVD. The fifth dielectric layer may be a silicon nitride layer formed by LPCVD. Similarly, the third buffer layer **228** may be omitted if the stress between the fifth dielectric layer and the exposed silicon layers is not too much.

Then, a self-aligned silicidation (salicide) process is performed to form metal silicide on exposed surfaces of silicon material on both the nonvolatile memory area and the logic area. Therefore, the exposed surface of the substrate **200** and other polysilicon layers will have metal silicide **232** formed thereon. Please note that since the top surfaces of the word lines **222a** and the erase gate **222b** are not exposed, no metal silicide can be formed on the top of the word lines **222a** and the erase gate **222b**.

In FIG. 2D, an etching stop layer **234** is formed above the substrate **200** to conformally covered the structure on the substrate **200**. The material of the etching stop layer **234** may be silicon nitride, for example. Then, a low-k dielectric layer **236** is formed above the substrate **200** to cover the structures formed on the substrate **200**. A process of chemical mechanical polishing (CMP) is subsequently performed to polish the whole wafer to remove an upper portion of the low-k dielectric layer **236**, and the CMP is stopped on the mask layer **210**. Hence, the thickness of the mask layer **210** is decreased further. The material of the low-k dielectric layer **236** is similar to the material of the low-k dielectric layer **136**, and hence omitted here.

FIGS. 3A-3D are cross-sectional diagrams showing a process of embedded nonvolatile memory according to some other embodiments of this disclosure. Since the processes before FIG. 3A are similar to FIGS. 1A-1C, the figures and the detailed descriptions are omitted here. In addition, the reference numbers in FIG. 3A representing the same or similar components are obtained by adding 200 to the reference numbers in FIG. 1C, and the meanings of the reference numbers in FIG. 3A representing the same or similar components are not described repeatedly. In FIGS. 3A-3D, the third polysilicon layer **222** in FIG. 2A is replaced by a third polysilicon layer **322** and an organic layer **324** in FIG. 3A. Therefore, the organic layer **324** and the third polysilicon layer **322** are non-selectively etched back to leave the third polysilicon layer **322** having a top surface not higher than the top surface of the control gate **308** in FIG. 3B. Thus, metal silicide can be avoided to be formed on the top surfaces of the word lines **322a** and the erase gate **322b**. The detailed descriptions of FIGS. 3A-3D are described below.

After the removal of the photoresist layer **121** in FIG. 1C, the exposed first buffer layer **316a** is then removed in FIG. 3A. The removal method of the exposed first buffer layer

316a may be wet etching, for example. A gate oxide layer **316b** is grown to cover the exposed surfaces of the substrate **300**, the floating gate **304a** and the common source **320**. The formation method of the gate oxide layer **316b** may be performed by thermal oxidation. Next, a third polysilicon layer **322** and an organic layer **324** is formed to cover the substrate **300**. The thickness of the third polysilicon layer **322** is smaller than a total thickness of the tunneling oxide layer **302a**, the floating gate **304a**, the middle dielectric layer **306a**, and the control gates **308**, such as in a range from about 400 Å to about 600 Å. The top surface of the organic layer is higher than the top surfaces of the gate stacks **314**. Therefore, the thickness of the organic layer **324** may be in a range from about 1000 Å to about 1500 Å according to some embodiments.

In FIG. 3B, the third polysilicon layer **322** and the organic layer **324** are non-selectively etched until the top surfaces of the third polysilicon layer **322** is lower than the top surfaces of the control gates **308**. According to some embodiments, the thickness of the remained third polysilicon layer **322** is in a range from about 600 Å to about 800 Å. In this step, an erase gate **322b** is formed. Then, the residue of the organic layer **324** is removed, and the removal may be performed by plasma ashing.

Next, a second buffer layer **326** and a fourth dielectric layer are sequentially formed above the substrate **300** to cover the structures on the substrate **300**. The fourth dielectric layer is anisotropically etched to form side cap layers **328a** on the word lines **322a** and a first middle cap layer **328b** on the erase gate **322b**, and some of the exposed second buffer layer **326** is consumed during the etching of the fourth dielectric layer. Next, the exposed third polysilicon layer **322** is further etched by using the side cap layers **328a** as an etching mask to form word lines **322a**. The second buffer layer **326** may be a silicon oxide layer formed by CVD. The fourth dielectric layer may be a silicon nitride layer formed by LPCVD. Similarly, the second buffer layer **326** may be omitted when the strains between the fourth dielectric layer and the exposed silicon layer is not too much.

In FIG. 3C, a third buffer layer **330** and a fifth dielectric layer are sequentially formed above the substrate **300**. The fifth dielectric layer is anisotropically etched to form third spacers **332a** on sidewalls of the word lines **322a** and a second middle cap layer **332b** on the erase gate **322b**. The exposed third buffer layer **330** is consumed during the etching of the fifth dielectric layer. The third buffer layer **330** may be a silicon oxide layer formed by CVD. The fifth dielectric layer may be a silicon nitride layer formed by LPCVD. Similarly, the third buffer layer **330** may be omitted when the strains between the fifth dielectric layer and the exposed silicon layer is not too much.

Then, a self-aligned silicidation (salicide) process is performed to form metal silicide **334** on exposed surfaces of silicon material on both the nonvolatile memory area and the logic area. Therefore, the exposed surface of the substrate **300** and other polysilicon layers will have metal silicide **334** formed thereon. Please note that since the top surfaces of the word lines **322a** and the erase gate **322b** are not exposed, no metal silicide can be formed on the top of the word lines **322a** and the erase gate **322b**.

In FIG. 3D, an etching stop layer **336** is formed above the substrate **300** to conformally covered the structure on the substrate **300**. The material of the etching stop layer **336** may be silicon nitride, for example. Then, a low-k dielectric layer **338** is formed above the substrate **300** to cover the structure formed on the substrate **300**. A process of chemical mechanical polishing (CMP) is subsequently performed to polish the

whole wafer to remove an upper portion of the low-k dielectric layer **338**, and the CMP is stopped on the mask layer **310**. Hence, the thickness of the mask layer **310** is decreased further. The material of the low-k dielectric layer **338** is similar to the material of the dielectric layer **136**, and hence omitted here.

Accordingly, this disclosure provides three different method to lower the top surfaces of the word lines and erase gates, hence the word lines and erase gates can have top surfaces lower than the top surfaces of the control gates. Furthermore, dielectric cap layers are formed on top surfaces of the word lines and the erase gates, and dielectric spacers are formed on sidewalls of the word lines. Therefore, no surfaces of the word lines and erase gates are exposed when self-aligned silicidation process is performed on both the nonvolatile memory area and the 28 HPM logic area, and no metal silicide can be formed on the word lines and erase gate. Consequently, during the CMP process, no metal silicide can be spread out to produce problems of current leakage and short circuits.

According to some embodiments of this disclosure, a non-volatile memory is provided, and nonvolatile memory comprises the following components. At least two gate stacks are located on a substrate, wherein the gate stacks each from bottom to top sequentially comprises a tunneling oxide layer, a floating gate, a middle dielectric layer, a control gate, and a mask layer. First spacers are located on sidewalls of the two gate stacks. A gate dielectric layer located on the exposed substrate. An erase gate is located between the two gate stacks and has a nonplanar top surface not higher than top surfaces of the control gates. Two word lines are located on outer sides of the two gate stacks and have nonplanar top surfaces not higher than the top surfaces of the control gates. Cap layers are located respectively on the erase gate and the word lines.

According to some other embodiments of this disclosure, a method of forming a nonvolatile memory is provided. Two gate stacks are formed on a substrate, wherein the gate stacks each from bottom to top sequentially comprises a tunneling oxide layer, a floating gate, a middle dielectric layer, a control gate, and a mask layer. First spacers are formed on sidewalls of the two gate stacks. A gate dielectric layer is formed on the exposed substrate. An erase gate between the two gate stacks and two word lines located on outer sides of the two gate stacks are simultaneously formed, wherein the erase gate and the two word lines have top surfaces not higher than top surfaces of the control gates. Composite cap layers are formed respectively on the top surfaces of the erase gate and the word lines.

According to some other embodiments of this disclosure, a method of forming a nonvolatile memory is provided. Two gate stacks are formed on a substrate, wherein the gate stacks each from bottom to top sequentially comprising a tunneling oxide layer, a floating gate, a middle dielectric layer, a control gate, and a mask layer. First spacers are formed on sidewalls of the two gate stacks. A gate dielectric layer is formed on the exposed substrate. A polysilicon layer and an organic layer are sequentially formed above the substrate, wherein the polysilicon layer has a thickness smaller than a total thickness of the tunneling oxide layer, the floating gate, the middle dielectric layer, and the control gates, as well as the organic layer has a top surface higher than top surfaces of the gate stacks. The organic layer and the polysilicon layer are non-selectively etched until the top surface of the polysilicon layer is not higher than top surfaces of the control gates. The residue of the organic layer is removed. A first dielectric layer is formed above the substrate. The first dielectric layer and the polysilicon layer thereunder are anisotropically etched until

the substrate is exposed. The polysilicon layer is etched to form an erase gate between the two gate stacks as well as word lines located on outer sides of the two gate stacks, and the first dielectric layer is etched to form first cap layers on the word lines and the erase gate.

According to some other embodiments of this disclosure, a method of forming a nonvolatile memory is provided. Two gate stacks are formed on a substrate, wherein the gate stacks each from bottom to top sequentially comprising a tunneling oxide layer, a floating gate, a middle dielectric layer, a control gate, and a mask layer. First spacers are formed on sidewalls of the two gate stacks. A gate dielectric layer is formed on the exposed substrate. A polysilicon layer and a first dielectric layer are sequentially formed above the substrate, wherein the polysilicon layer has a thickness smaller than a total thickness of the tunneling oxide layer, the floating gate, the middle dielectric layer, and the control gates. The first dielectric layer and polysilicon layer thereunder are anisotropically etched until the substrate is exposed. The polysilicon layer is etched to form an erase gate between the two gate stacks as well as word lines located on outer sides of the two gate stacks, and the first dielectric layer is etched to form first cap layers on the word lines and the erase gate. An organic layer is formed on the exposed substrate. The exposed word lines and the exposed erase gate are etched until the erase gate and the word lines have top surfaces lower than top surfaces of the control gates. The organic layer is removed. A second dielectric layer is formed above the substrate. The second dielectric layer is anisotropically etched to form second spacers on outer sidewalls of the word lines and second cap layers on the word lines and the erase gate.

The foregoing outlines features of several embodiments so that those skilled in the art may better understand the aspects of the present disclosure. Those skilled in the art should appreciate that they may readily use the present disclosure as a basis for designing or modifying other processes and structures for carrying out the same purposes and/or achieving the same advantages of the embodiments introduced herein. Those skilled in the art should also realize that such equivalent constructions do not depart from the spirit and scope of the present disclosure, and that they may make various changes, substitutions, and alterations herein without departing from the spirit and scope of the present disclosure.

What is claimed is:

1. A method of forming a nonvolatile memory, the method comprising:
forming two gate stacks on a substrate, wherein the gate stacks each from bottom to top sequentially comprises a tunneling oxide layer, a floating gate, a middle dielectric layer, a control gate, and a mask layer;
forming first spacers on sidewalls of the two gate stacks;
forming a gate dielectric layer on an exposed portion of the substrate;
sequentially forming a polysilicon layer and an organic layer above the substrate, wherein the polysilicon layer has a thickness smaller than a total thickness of the tunneling oxide layer, the floating gate, the middle dielectric layer, and the control gates, as well as the organic layer has a top surface higher than top surfaces of the gate stacks;
etching the organic layer and the polysilicon layer until the top surface of the polysilicon layer is not higher than top surfaces of the control gates;
removing a residue of the organic layer;
forming a first dielectric layer above the substrate; and
anisotropically etched the first dielectric layer and the polysilicon layer thereunder until the substrate is

exposed, wherein the polysilicon layer is etched to form an erase gate between the two gate stacks as well as word lines located on outer sides of the two gate stacks, and the first dielectric layer is etched to form first cap layers on the word lines and the erase gate.

2. The method of claim 1, wherein the first spacers each comprises an inner silicon oxide layer and an outer silicon nitride layer.

3. The method of claim 1, further comprising:
forming a second dielectric layer above the substrate; and
anisotropically etching the second dielectric layer until the substrate is exposed to form second spacers on outer sidewalls of the word lines.

4. The method of claim 1, further comprising:
forming a buffer layer between the polysilicon layer and the first dielectric layer.

5. The method of claim 1, wherein the word lines are formed by using the first cap layers as an etching mask.

6. The method of claim 1, wherein the first dielectric layer comprises a silicon nitride layer.

7. The method of claim 3, further comprising:
forming a buffer layer between the first dielectric layer and the second dielectric layer.

8. The method of claim 3, wherein the second dielectric layer comprises a silicon nitride layer.

9. The method of claim 1, further comprising:
forming a metal silicide layer in the substrate exposed by the two gate stacks, the first spacers, the erase gate, the word lines, and the first cap layers.

10. A method of forming a nonvolatile memory, the method comprising:

forming two gate stacks on a substrate, wherein the gate stacks each from bottom to top sequentially comprises a tunneling oxide layer, a floating gate, a middle dielectric layer, a control gate, and a mask layer;

forming first spacers on sidewalls of the two gate stacks;
forming a gate dielectric layer on a first exposed portion of the substrate;

sequentially forming a polysilicon layer and a first dielectric layer above the substrate, wherein the polysilicon layer has a thickness smaller than a total thickness of the tunneling oxide layer, the floating gate, the middle dielectric layer, and the control gates;

anisotropically etching the first dielectric layer and polysilicon layer thereunder until a second portion of substrate is exposed, wherein the polysilicon layer is etched to form an erase gate between the two gate stacks as well as word lines located on outer sides of the two gate stacks, and the first dielectric layer is etched to form first cap layers on the word lines and the erase gate;

forming an organic layer on the second exposed portion of the substrate;

etching the word lines and the erase gate until the erase gate and the word lines have top surfaces lower than top surfaces of the control gates;

removing the organic layer;

forming a second dielectric layer above the substrate; and
anisotropically etching the second dielectric layer to form second spacers on outer sidewalls of the word lines and second cap layers on the word lines and the erase gate.

11. The method of claim 10, wherein the first spacers each comprises an inner silicon oxide layer and an outer silicon nitride layer.

12. The method of claim 10, wherein the first dielectric layer and the second dielectric layer each comprises a bottom silicon oxide layer and a top silicon nitride layer.

13. The method of claim 10, wherein the etching of the word lines and the erase gate is performed by dry etching.

14. The method of claim 13, wherein the dry etching is performed in a poly etcher by using SF_6 as a plasma source.

15. The method of claim 13, wherein the dry etching is performed in a remote plasma etcher by using $\text{C}_x\text{H}_y\text{F}_z$ and oxygen as a plasma source, and the $\text{C}_x\text{H}_y\text{F}_z$ is CH_2F_2 , CHF_3 , CF_4 , C_2F_6 , C_3F_8 , C_4F_6 , or C_5F_8 .

16. The method of claim 10, further comprising:

removing a portion of the organic layer to expose the word lines and the erase gate before etching the exposed word lines and the exposed erase gate.

17. The method of claim 10, further comprising:

forming a buffer layer between the first dielectric layer and the second dielectric layer.

18. The method of claim 10, further comprising:

forming a metal silicide layer in the substrate exposed by the two gate stacks, the first spacers, the erase gate, the word lines, the second spacers, the first cap layers, and the second cap layers.

19. The method of claim 10, further comprising:

forming an etching stop layer on the second dielectric layer and the substrate.

20. The method of claim 19, further comprising:

forming a low-k dielectric layer on the etching stop layer, wherein a dielectric constant of the low-k dielectric layer is smaller than a dielectric constant of silicon dioxide.

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